

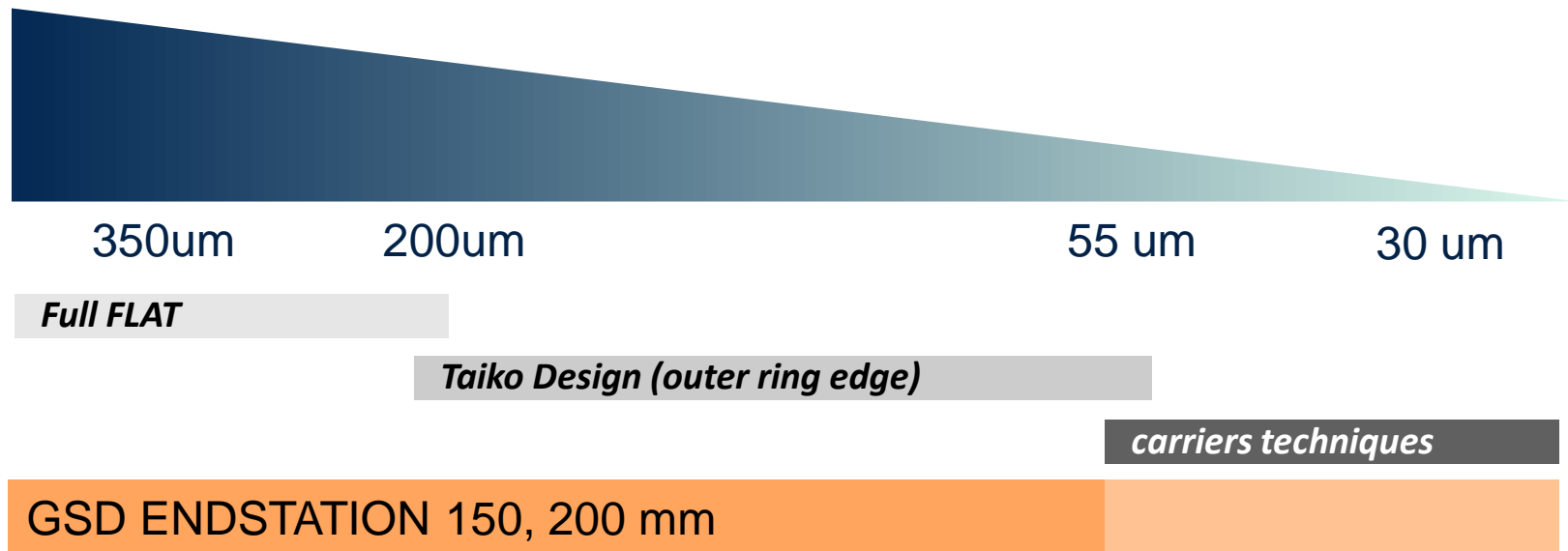
150mm Thin Wafer Handling Upgrade for GSD Platform

GSD 200E², HE/VHE



Power Devices, 3D Packaging Application Specifics

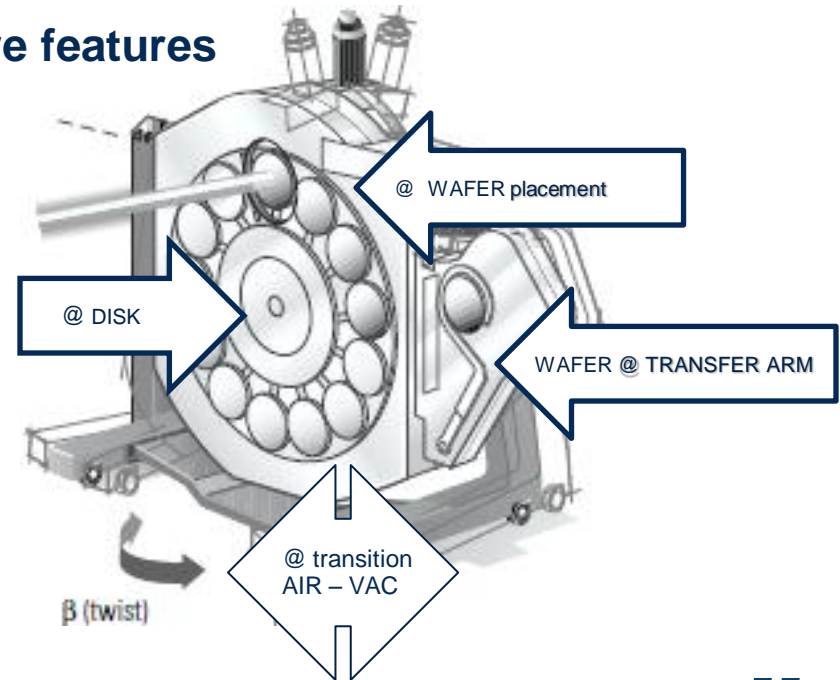
Axcelis Thin Wafer Solution



- **GSD Platform with Axcelis Thin Wafer Handling Options**
 - **150mm** thin wafers in production has increased significant in past 10 years
 - New generation upgrade enables wafer thickness of 215 um (without tape) and down to 55um with annulus ring and protective tape
- **GSD wafer handling system automatically handles both thin and standard wafers**

Technical Challenges Being Addressed

- Causes of mechanical stress on thin wafers
 - In-air locations at robot level, flat aligner
 - During transition from in air to vacuum
 - In vacuum:
 - Transfer arm
 - Wafer holder and disk
 - Combination of hardware and software features

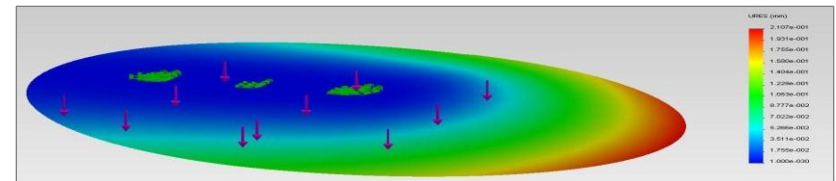


Eliminate Unwanted Forces With Innovative Robot End-effector

- Optimization of in-air wafer contact: new vacuum channel geometry
- Minimal deflection on thin substrate
- Low contamination wafer pan: carbon fiber, teflon cover



New End-effector Design with Material Designed for Low Metal Contamination



Optimize Deflection, Minimal Contact



Old End-effector – Creates Deflection



NEW End-effector – No Deflection

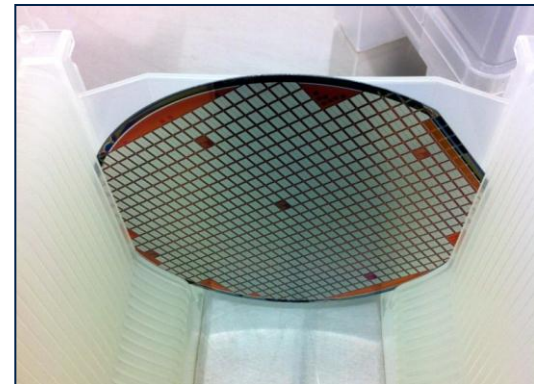
Innovative Solution for Disk Clamping



FORMER VERSION
Bowling of wafer on pad

**INNOVATIVE
SOLUTION**
For Perfect
Wafer Positioning

Current Capabilities on 150mm Thin Wafers



Currently in Manufacturing Environment

Si Wafer Design	Wafer Thickness (μm)	Disk spin speed (rpm)
Full Flat	675 - 300	1210
	300 - 250	815
	250 - 215	613
Thin with outer ring (*) ring thickness 625um, 2mm wide	> 200 - 120	815
	120 - 50	613
Thin with outer ring (*) ring thickness 450um, 7mm wide	200 - 130	815
Thin with outer ring (*) ring thickness 450um, 7mm wide	130 - 50	613

(*) protective tape